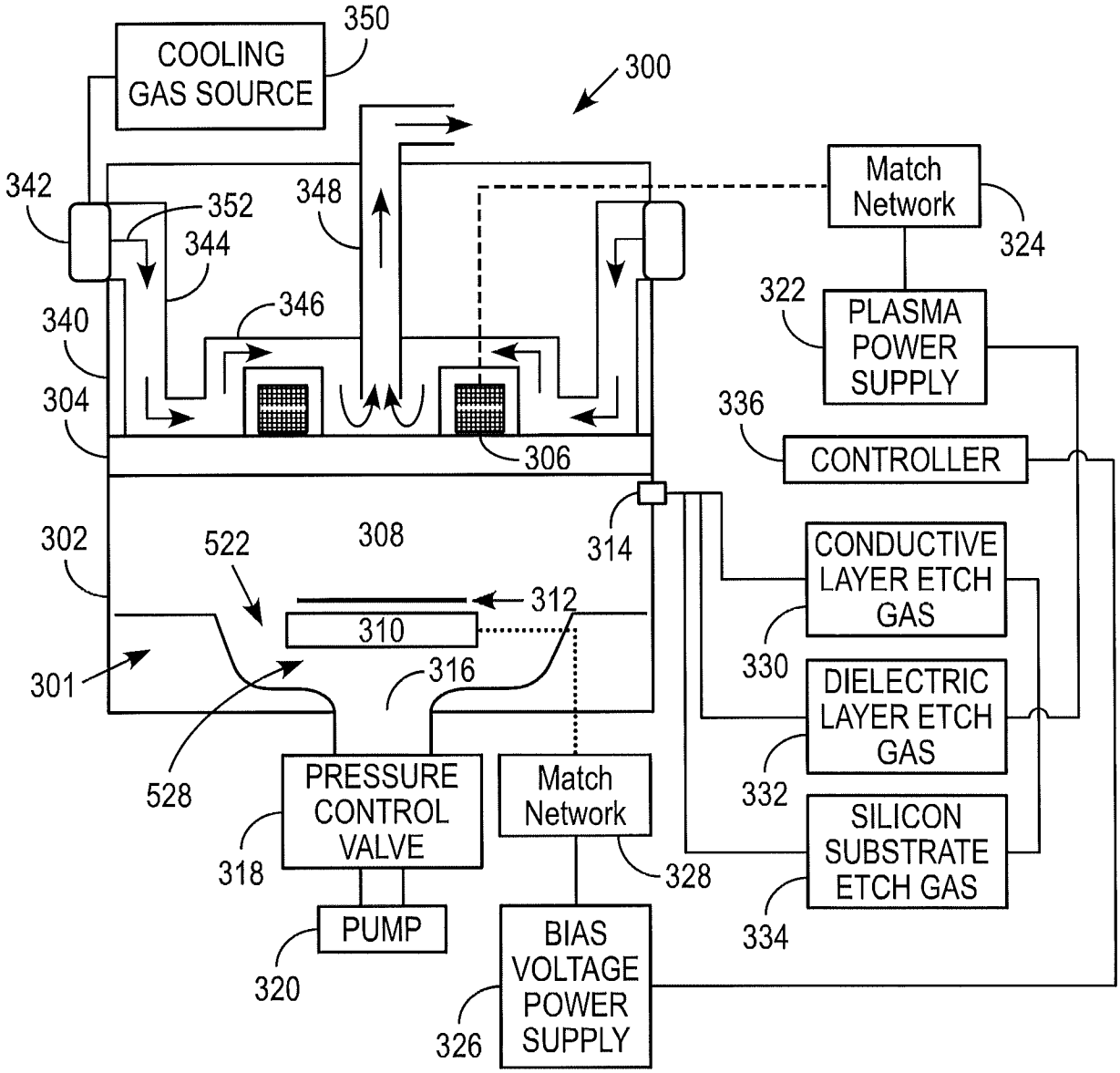

COOLING GAS SOURCE
350
300
342
352
348
344
346
340
304
306
Match Network
324
322
PLASMA POWER SUPPLY
336
CONTROLLER
302
522
308
314
312
310
301
316
528
CONDUCTIVE LAYER ETCH GAS
330
DIELECTRIC LAYER ETCH GAS
332
SILICON SUBSTRATE ETCH GAS
334
PRESSURE CONTROL VALVE
318
Match Network
328
PUMP
320
BIAS VOLTAGE POWER SUPPLY
326

FIG. 1

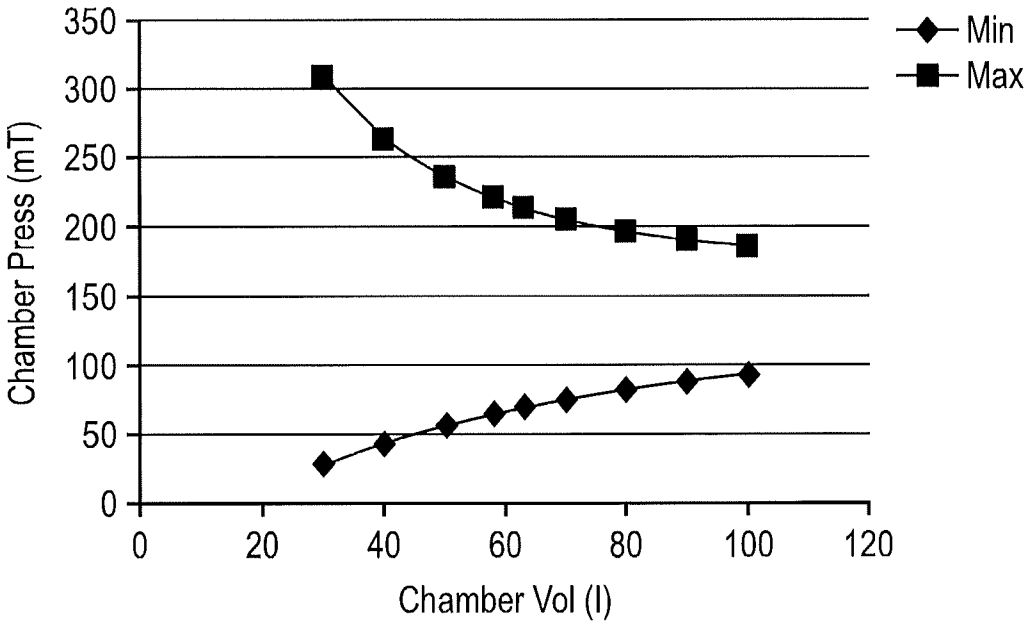

350
300
250
200
150
100
50
0
Chamber Press (mT)
0
20
40
60
80
100
120
Chamber Vol (l)
Min
Max

FIG. 2

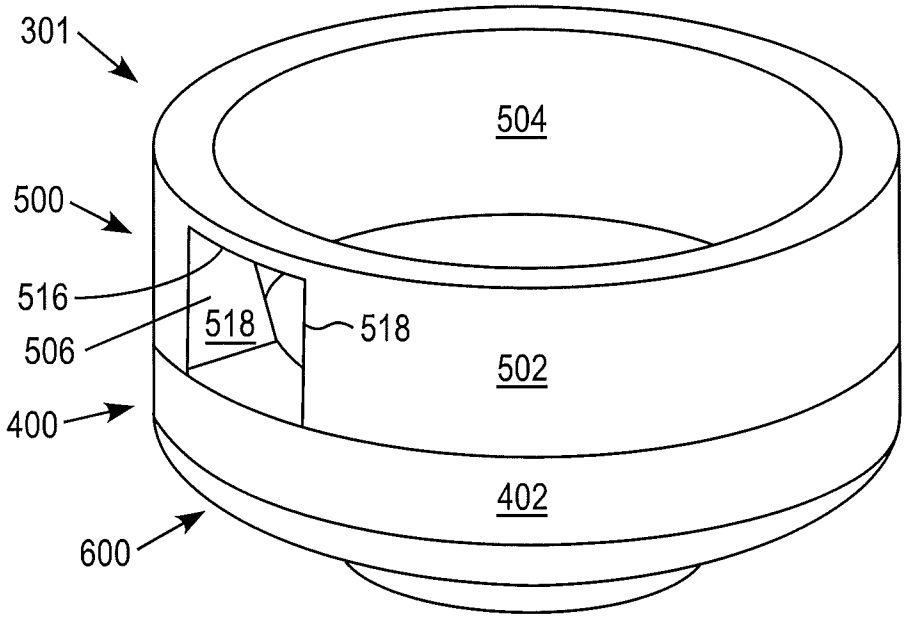


FIG. 3

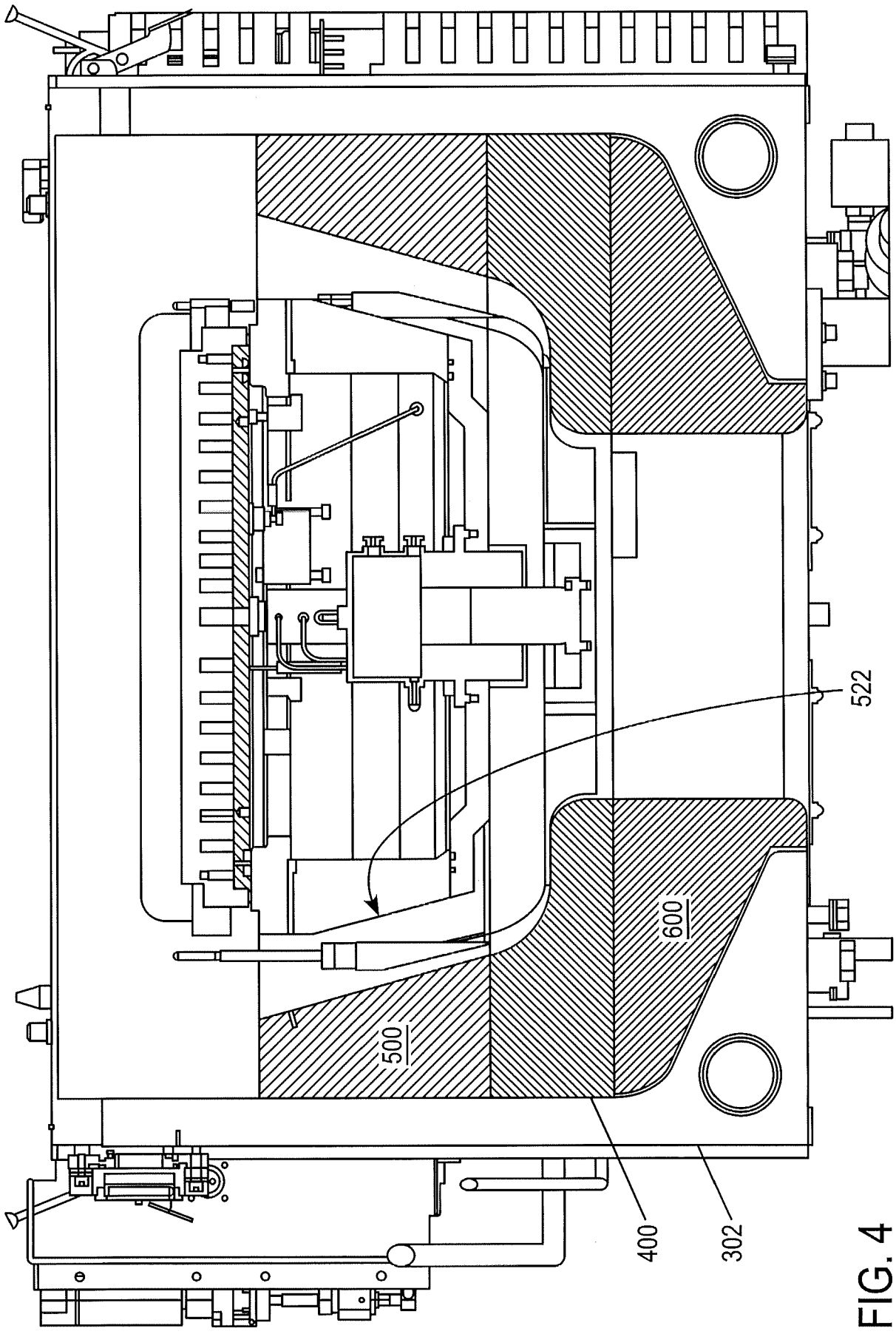


FIG. 4

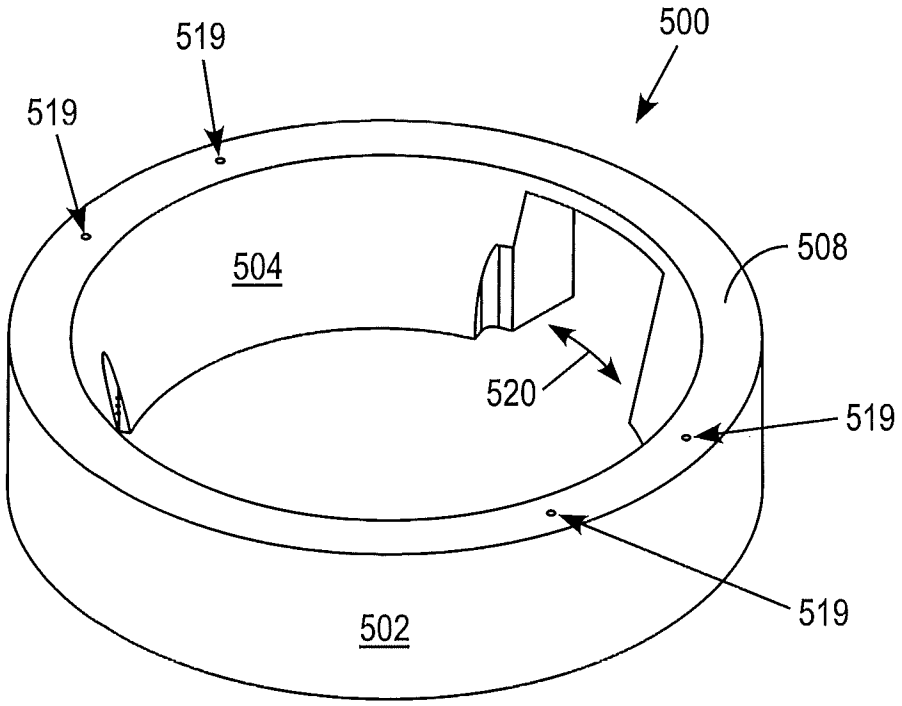

519
519
500
504
508
520
519
519
502

FIG. 5A

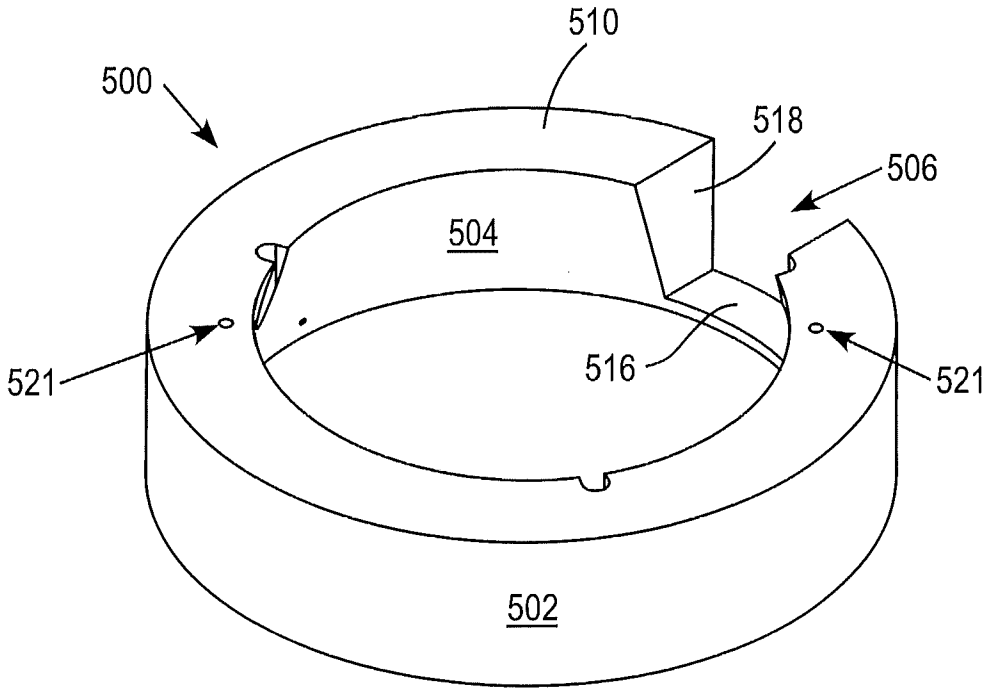

510
500
518
506
504
521
516
521
502

FIG. 5B

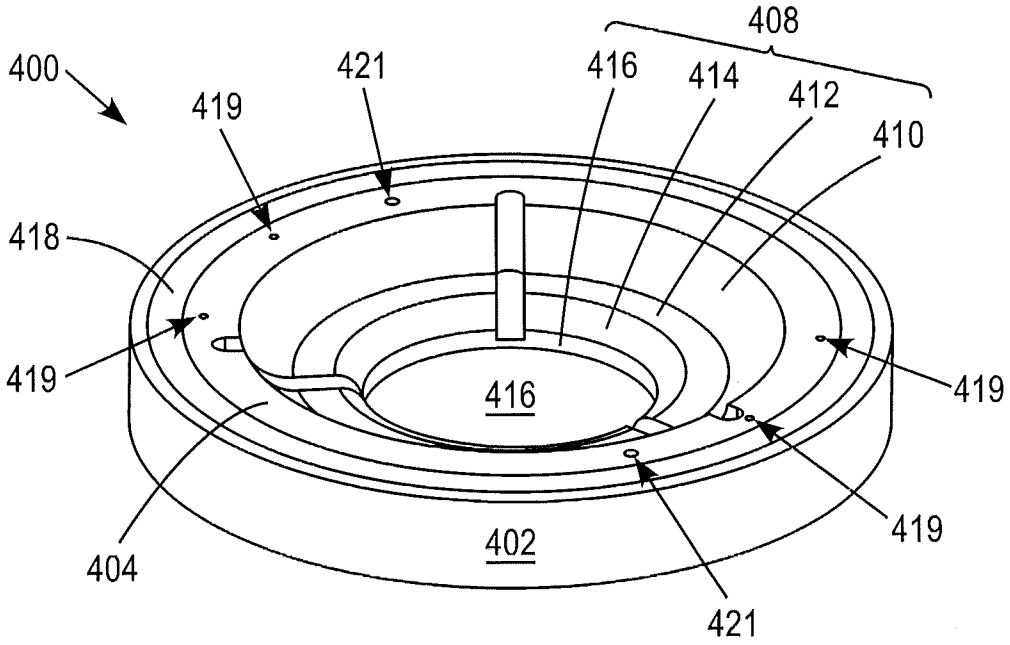

400
419
421
408
416
414
412
410
418
419
416
419
404
402
419
421

FIG. 6A

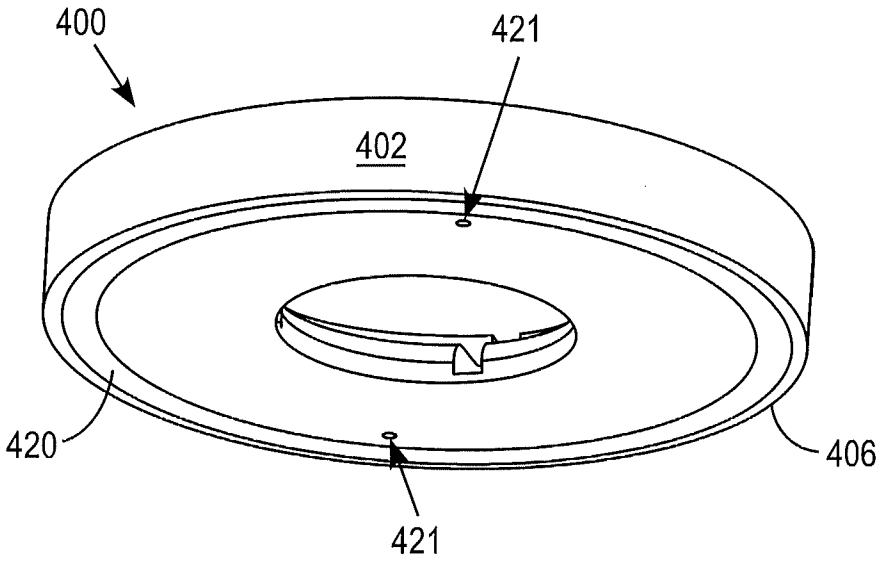

400
421
402
420
406
421

FIG. 6B

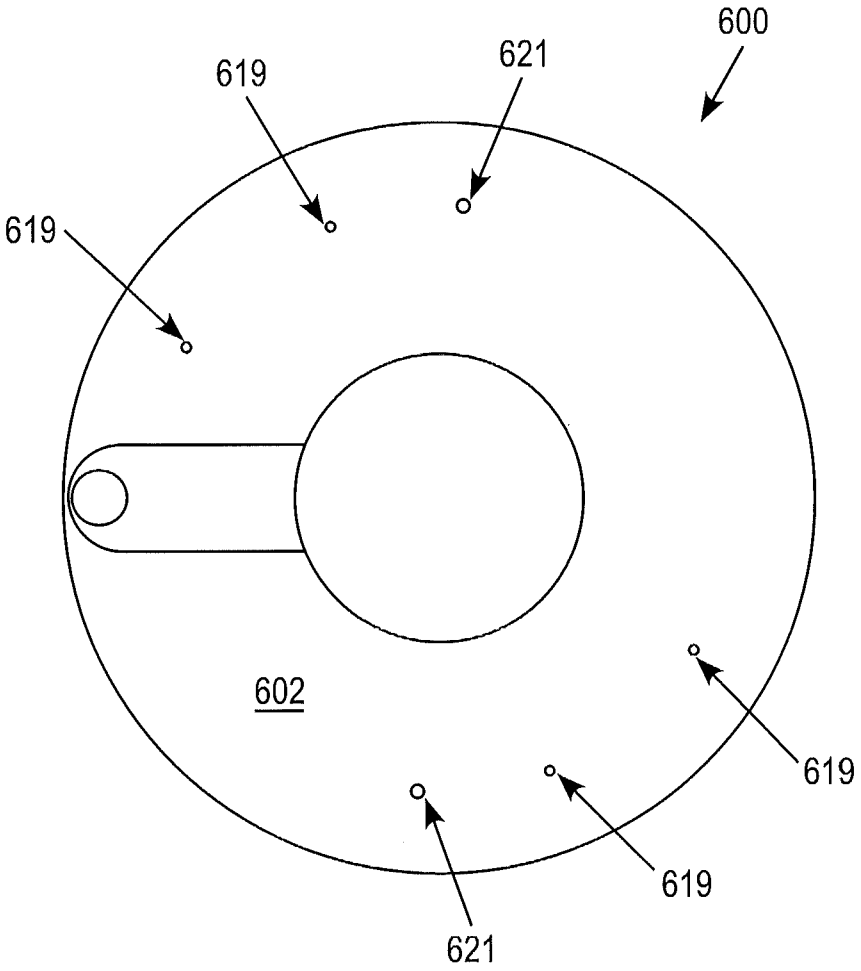


FIG. 7A

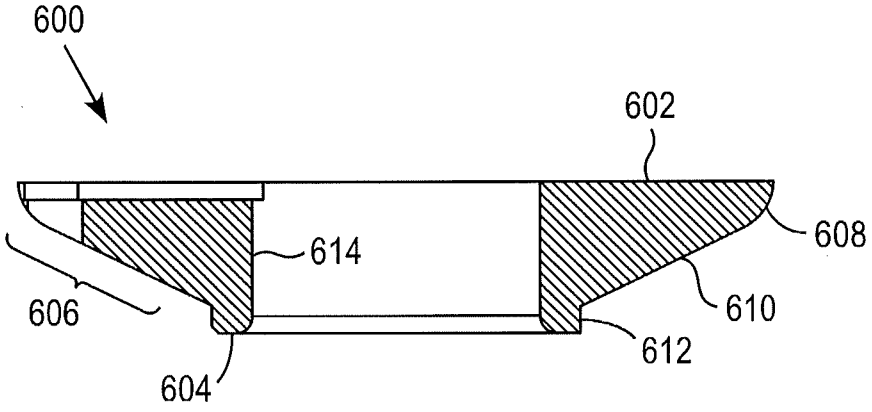


FIG. 7B